D. Thin Film Process Technology 분과

2021년 1월 27일(수), 13:00–14:30 / 채널 A

[WA3-D] Thin Film Process Ⅱ

좌장: 엄태용 박사 (KRICT), 전우진 교수 (경희대학교)

WA3-D-1 **13:00-13:15**	**Advanced Atomic Layer Deposition of Metal Oxide Films with Discrete Feeding Method** Jae Chan Park[1], Sang Gil Lee[2], Seung Jo Yoo[2], Ji Hyeon Lee[2], Jae Hyuck Jang[2], Woo-Hee Kim[1], and Tae Joo Park[1] *[1]Department of Materials Science and Chemical Engineering, Hanyang University,* *[2]Center for Research Equipment, KBSI*
WA3-D-2 **13:15-13:30**	**Atomic Layer Deposition of Titanium Dioxide Thin Films Using $Cp^*Ti(OMe)_3$ as a Precursor** Hong Keun Chung[1,2], Tae Joo Park[2], and Seong Keun Kim[1] *[1]Electronic Materials Research Center, KIST,* *[2]Department of Materials Science and Chemical Engineering, Hanyang University*
WA3-D-3 **13:30-13:45**	**Integrating SiO_2 Selective Deposition Process to Atomic Layer Etching of Ru for Self-aligned Nanofabrication** Sumaira Yasmeen, Byeongguk Ko, Bon Wook Gu, and Han-Bo-Ram Lee *Incheon National University*
WA3-D-4 **13:45-14:00**	**Atomic Layer Deposition of Tin Selenide (Sn_xSe_{1-x}) Thin Films Using $Sn^{IV}(NMe_2)_4$ and $Se(SiMe_3)_2$ with NH_3 Co-reagent** Jeong Woo Jeon[1,2], Chanyoung Yoo[1,2], Woohyun Kim[1,2], Wonho Choi[1,2], Byongwoo Park[1,2], Eui-sang Park[1,2], Manick Ha[1,2], Yoon Kyeung Lee[3], and Cheol Seong Hwang[1,2] *[1]Department of Materials Science and Engineering, Seoul National University,* *[2]Inter-University Semiconductor Research Center, Seoul National University,* *[3]Division of Advanced Materials Engineering, Jeonbuk National University*
WA3-D-5 **14:00-14:15**	**Selective Wet Etching of Si Versus $Si_{1-x}Ge_x$ in Single- and Multi-Layer with TMAH Etchant** 최용준, 변대섭, 조충희, 이기석, 윤동민, 고대홍 *연세대학교 신소재공학과*
WA3-D-6 **14:15-14:30**	**철회**